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Substitute for form 1449A/PTO			Complete If Known		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>			Application Number	10/616,603	
			Filing Date	10 July 2003	
			First Named Inventor	Christophe Pierrat et al.	
			Group Art Unit		
			Examiner Name		
Sheet	1	of	2	Attorney Docket Number	FTIS 1001-1

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code ² (If known)			
UX	A1	5,121,256		Corle et al.	06-09-1992	
UX	A2	5,469,299		Nagano	11-21-1995	
UX	A3	5,982,558		Further et al.	11-09-1999	
UX	A4	6,198,576		Matsuyama	03-06-2001	
UX	A5	6,522,484		Schuster	02-18-2003	
	A6					
	A7					
	A8					
	A9					
	A10					
	A11					
	A12					
	A13					
	A14					
	A15					
	A16					
	A17					
	A18					
	A19					
	A20					

FOREIGN PATENT DOCUMENTS								
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		Office ³	Number ⁴	Kind Code ⁵ (If known)				
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	B10							

Examiner Signature <i>Deborah L. Harris</i>	Date Considered 09/30/05
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¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that Issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 2 of 2

Complete If Known

Application Number	10/616,603
Filing Date	10 July 2003
First Named Inventor	Christophe Pierrat et al.
Group Art Unit	
Examiner Name	
Attorney Docket Number	FTIS 1001-1

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
WD	C1	FRENCH, ROGER H., et al., "Fluoropolymers for 157nm Lithography: Optical Properties from VUV Absorbance and Ellipsometry Measurements," SPIE Proceedings, Microlithography 2000, 12 pages.	
WD	C2	FLAGELLO, DONIS G., et al., "High-numerical-aperture effects in photoresist," Applied Optics 36(34) (1 Dec 1997) 8944-8951.	
WD	C3	FRENCH, ROGER H., et al., "Materials Design and Development of Fluoropolymers for Use as Pellicles in 157nm Photolithography," Optical Microlithography XIV, Proceedings of SPIE vol. 4346 (2001).	
WD	C4	PIERRAT, CHRISTOPHE, et al., "The MEF Revisited: Low k1 Effects versus Mask Topography Effects," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (25 Feb 2003).	
WD	C5	CHIBA, YUJI, et al., "New generation projection optics for ArF lithography," Optical Microlithography XV, Proceedings of SPIE Vol. 4691 (2002), 679-686.	
WD	C6	BAEK, SO-YEON, et al., "Simulation Study of Process Latitude for Liquid Immersion Lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 11 pages.	
WD	C7	PENDRY, J.B., et al., "Near-field lenses in two dimensions," J. Phys.: Condens. Matter 14 (2002) 8463-8479.	
WD	C8	OBER, CHRISTOPHER K., "Polymer Surfaces and Surface Analysis," Nanobiotechnology MSE 563/AEP 663 (2000), 43 pages.	
WD	C9	HAFEMAN, SCOTT, et al., "Simulation of imaging and stray light effects in immersion lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 13 pages.	

Examiner
Signature

David Charles Davis

Date
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